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843.41042X00

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): K. Hayano, et al.

Application No.: 10/025,457

Filing Date: December 26, 2001

For: METHOD OF MANUFACTURING PHOTOMASK AND METHOD OF  
MANUFACTURING SEMICONDUCTOR INTEGRATED CIRCUIT  
DEVICE

Art Unit: 1756

Examiner: S. Mohamedulla

**AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

March 30, 2004

Sir:

In response to the Office Action mailed December 31, 2003, please amend the above-identified application as listed in the following, and as set forth on the following pages:

Amendments to the Claims; and

Remarks are included following the amendments.